

## Description

The Asymmetric P-Nylon filter utilizes the proven defect-reducing Nylon membranes configured into a new asymmetric pore geometry. This tapered pore design, with an open upstream structure and a fine downstream region, enables extremely low operating pressures. The Nylon Effect <sup>1</sup>, which has proven to significantly reduce microbridge and cone defects in 193 nm resist and BARC chemistries can now be applied to all lithography applications. The XP option is available for advanced lithography processes.

## Features

- Naturally hydrophilic (no surface modifications)
- Quick venting
- 100% integrity tested
- Manufactured in a cleanroom environment
- Reduces defects by sieving and adsorption
- Minimized organic extractables by XP option
- XP option guarantees low organic, metal and particle cleanliness for the most advanced processes.



## Benefits

- Reduce filter start-up and tool downtime
- Minimize chemical wastes

## Specifications

### Materials of Construction

Components	Materials
Filter Medium	Asymmetric hydrophilic Nylon 6,6
Support and Drainage	HDPE <sup>2</sup>
Core, Cage and End Caps	HDPE
O-ring Options	FEP Encapsulated fluoroelastomer, Perfluoroelastomer

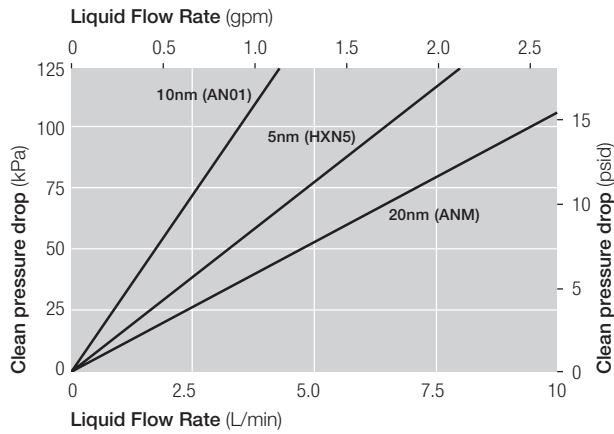
	ABD Filters					
	2 nm	5 nm	10 nm	20 nm	40 nm	0.15 µm
Removal Ratings						
Filter Areas (10" / std. Dia.)	1.7 m <sup>2</sup>	1.1 m <sup>2</sup>	1.3 m <sup>2</sup>	1.3 m <sup>2</sup>	1.2 m <sup>2</sup>	1.2 m <sup>2</sup>
Filter Areas (10" / G2. Dia.)	2.2 m <sup>2</sup>					
Maximum Operating Temperature	50 °C / 122 °F					
Maximum Forward Differential Pressure	275 kPa @ 20 °C / 40 psid @ 68 °F					

<sup>1</sup> Adsorption of hardly soluble polymer components by the unique surface characteristics of the P-Nylon membrane.

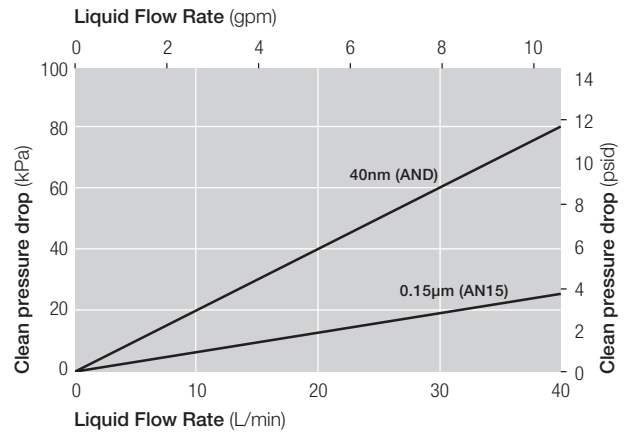
<sup>2</sup> High density polyethylene.

## Typical Flow Characteristics - 1 cP fluid, 20 °C

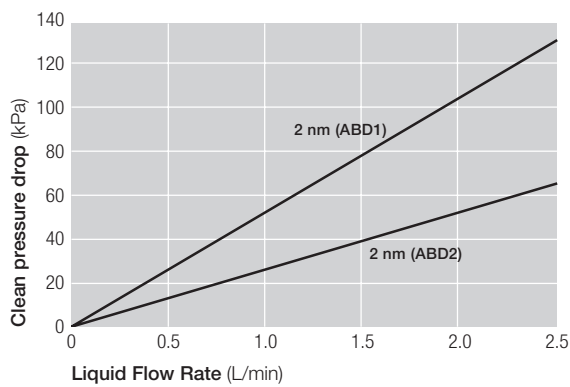
### ABD1



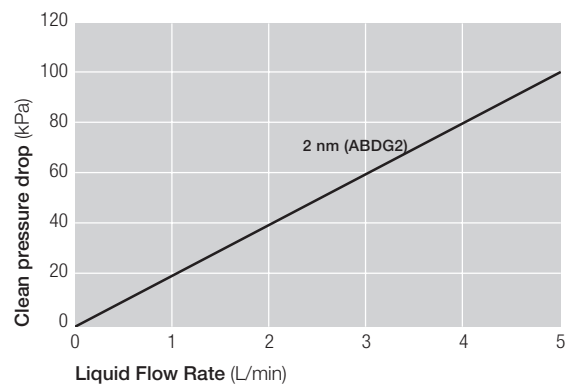
### ABD1



### ABD1 / ABD2



### ABDG2



## Part Numbers / Ordering Information<sup>3,4</sup>

ABD 1 2 3 E 4

**Table 1**

Code	Nominal length / dia (mm / in)	
1	254 / 10	70 / 2.75
2	508 / 20	70 / 2.75
3	762 / 30	70 / 2.75
G1	254 / 10	82 / 3.25
G2	508 / 20	82 / 3.25

**Table 2**

Code	Removal Ratings
XN2L	2 nm
HXN5	5 nm
AN01	10 nm
ANM	20 nm
AND	40 nm
AN15	0.15 µm

**Table 3**

Code	Configurations
3	222 O-ring open end flat closed end
7	226 O-ring open end fin on closed end
8	222 O-ring open end fin on closed end

**Table 4**

Code	O-ring Materials
H1	FEP Encapsulated fluoroelastomer
H11	Perfluoroelastomer

<sup>3</sup> Filter elements may not be available in all configurations. Contact your local Pall representative for availability.

<sup>4</sup> For XP treatment option, add -XP to the end of a part number for 10 - 20 nm removal ratings and 10 - 20 inches. (XP treatment is standard for 2 nm / 5 nm product)



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